

AMENDMENT TRANSMITTAL LETTER

Docket No.
M4065.0353/P353-A

DEC 26 2002

Application No.
09/982,954Filing Date
October 22, 2001Examiner
Karla MooreArt Unit
1763

Applicant(s): Gurtej Sandhu, et al.

Invention: ATOMIC LAYER DOPING APPARATUS AND METHOD

TO THE COMMISSIONER FOR PATENTS

Transmitted herewith is an amendment in the above-identified application.

The fee has been calculated and is transmitted as shown below.

CLAIMS AS AMENDED					
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate	
Total Claims	19	- 20 =		x	0.00
Independent Claims	3	- 3 =		x	0.00
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					
Other fee (please specify):					
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:					0.00

 Large Entity Small Entity No additional fee is required for this amendment. Please charge Deposit Account No. _____ in the amount of \$ _____.
A duplicate copy of this sheet is enclosed. A check in the amount of \$ _____ to cover the filing fee is enclosed. Payment by credit card. Form PTO-2038 is attached. The Commissioner is hereby authorized to charge and credit Deposit Account No. 04-1073
as described below. A duplicate copy of this sheet is enclosed. Credit any overpayment. Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.Thomas J. D'Amico
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Dated: December 26, 2002

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Gurtej Sandhu et al.,

Application No.: 09/982,954

Group Art Unit: 1763

Filed: October 22, 2001

Examiner: Karla Moore

For: ATOMIC LAYER DOPING APPARATUS
AND METHOD

HSB
12/31/02
MW

AMENDMENT

Commissioner for Patents
Washington, DC 20231

Dear Sir:

Responsive to the Office Action of September 26, 2002, rejecting claims 1-17, please amend the above-identified U.S. patent application as follows:

In the Claims:

Please add new claims 46 and 47.

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46. (new) An atomic layer doping apparatus comprising:

B1
a first atomic layer doping region for depositing a first dopant species on a first substrate as a monolayer;

a second atomic layer doping region for diffusing said first dopant species in said first substrate, said first and second doping regions being chemically isolated from one another by an inert gas curtain, wherein said inert gas curtain is provided at a higher pressure than said first dopant species; and,